

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 62-286579

(43)Date of publication of application : 12.12.1987

(51)Int.Cl.

B05D 1/40

B05D 3/06

G11B 7/26

H01L 21/30

H05K 3/06

(21)Application number : 61-130221

(71)Applicant : TOSHIBA CORP

(22)Date of filing : 06.06.1986

(72)Inventor : OGAWA SHIGERU

ITOU AKIKO

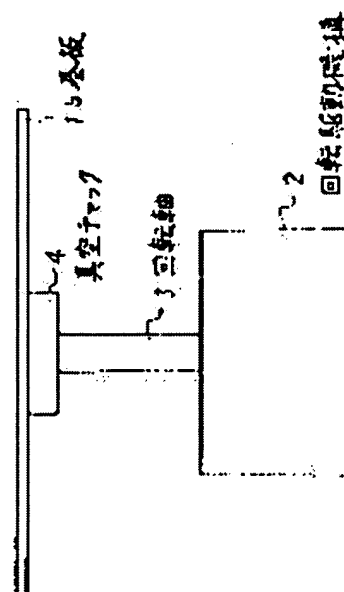
KATAOKA YOSHINORI

(54) METHOD FOR COATING SUBSTRATE WITH RESIST

(57)Abstract:

PURPOSE: To form a film having a thickness almost uniform up to the corner parts thereof by enhancing the wettability of a substrate with a resist, in forming a resist film to the substrate by a rotary coating method, by preliminarily applying pretreatment due to irradiation of ultraviolet rays and heat treatment to the substrate.

CONSTITUTION: For example, in applying a resist to a square glass substrate 1b, said square substrate 1b is placed on a hot plate held to set temp. of 150W200° C while pretreatment using a 65W low pressure mercury lamp as an ultraviolet ray source to irradiate the substrate with ultraviolet rays for 120sec is performed. By this method, the resist coating surface of the square substrate 1b is purified and the wettability thereof with the resist is improved. In this state, the square substrate 1b is sucked to and supported by the vacuum chuck 4 on a rotary shaft 3 rotating by a rotary drive mechanism 2 and coated with the resist according to a rotary coating method to form a film having a thickness uniform in the side and angle directions of the substrate.



LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or

application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]

Copyright (C); 1998,2003 Japan Patent Office